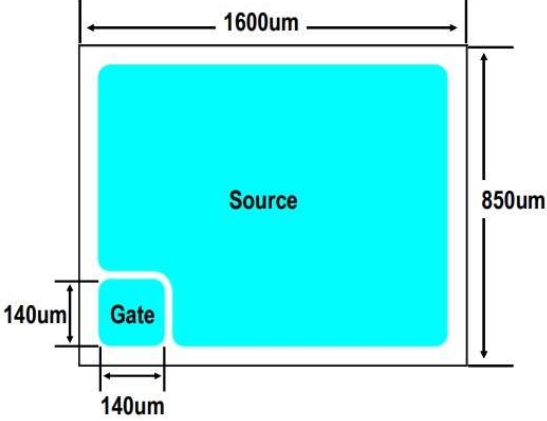


MOSFET Metal-Oxide-Semiconductor Field-Effect Transistor
20V N-Channel MOSFET

Bonding Pad Information		Chip Information	
		Die Size (with Scribe Line)	1,650μm x 900μm
		Gate Pad Size	140μm x 140μm
		Source Pad Size	Full metalized surface of source region
		Scribe Line Size	50μm
		Wafer Size	6inches
		Wafer Thickness	5mils
		Metallization	Front Side: Al/Si/Cu : 4μm
			Back Side: Ti/Ni/Ag : 1.4μm
		Recommended Wire Bonding	
		Gate Pad	1.5 mil x 1 (Cu wire)
		Source Pad	2.0 mil x 16 (Cu wire)
		Gross Die	10,000ea

Maximum Ratings (TA=25°C unless otherwise noted)

Parameter	Symbol	Value	Unit
Drain-Source Voltage	V _{DSS}	20	V
Gate-Source Voltage	V _{GSS}	±12	V
Drain Current-Continuous @ T _C =25°C	I _D	11	A
Drain Current-Pulsed	I _{DM}	70	A
Operating Junction Temperature Range	T _J	-55 to +150	°C

Electrical Characteristics (TA=25°C unless otherwise noted)

Parameter	Symbol	Conditions	Min.	Typ.	Max.	Unit
OFF CHARACTERISTIC						
Drain-Source Breakdown Voltage	BV _{DSS}	V _{GS} =0V, I _D =250uA	20	-	-	V
Drain-Source Leakage Current	I _{DSS}	V _{GS} =0V, V _{DS} =16V	-	-	1	uA
Gate-Source Leakage Current	I _{GSS}	V _{GS} =±12V, V _{DS} =0V	-	-	±10	uA
ON CHARACTERISTIC						
Gate Threshold Voltage	V _{GS(TH)}	V _{GS} =V _{DS} , I _D =250uA	0.5	0.8	1.2	V
Static Drain-Source On-Resistance	R _{DS(ON)}	V _{GS} =4.5V, I _D =5.5A	4.5	6.0	7.2	mΩ
		V _{GS} =3.7V, I _D =5.5A	5.0	7.0	8.2	
		V _{GS} =2.5V, I _D =5.5A	6.0	9.0	10.2	
		DYNAMIC CHARACTERISTICS				
Input Capacitance	C _{iSS}	V _{GS} =0V, V _{DS} =10V, f=1MHz	-	1310	-	pF
Output Capacitance	C _{oSS}		-	264	-	
Reverse Transfer Capacitance	C _{rSS}		-	235	-	
DRAIN-SOURCE DIODE CHARACTERISTICS AND MAXIMUM RATINGS						
Drain-Source Diode Forward Voltage	V _{SD}	V _{GS} =0V, I _S =1A	-	0.85	1.2	V

NOTE:

- The data tested by pulsed, pulse with ≤ 300us, duty cycle ≤ 2%.
- R_{DS(ON)} calculated by DFN3x3-6L package type.
- ESD protected 2kV for DFN3x3-6L.